. . .

## **AMENDMENTS TO THE SPECIFICATION**

## Please replace the paragraph at page 2, line 6, with the following rewritten paragraph:

Accordingly, there is examined a new processing method that uses no resist process. As one example, there is being proposed a plasma processing apparatus equipped with a microplasma source 99 as shown in Fig. 16. The construction is proposed in detail in, for example, the first patent reference of the company's own application that has not yet been laid open: Japanese Patent Application No. 2002-254324 that has been published as Japanese Unexamined Patent Publication No. 2004-146773 which was filed as claiming priority of Japanese Patent Application No. 2002-254324.